

L Number	Hits	Search Text	DB	Time stamp
-	36	(optical adj waveguide).ti.and facet and etch\$3	USPAT; US-PGPUB	2002/11/06 14:49
-	184	method adj2 forming near2 (optical adj (component or waveguide))	USPAT; US-PGPUB	2002/11/06 10:55
-	62	(channel adj waveguide)and etch\$3 and mask\$3 and light adj transmit\$3	USPAT; US-PGPUB	2002/11/01 08:26
-	329	(channel adj waveguide)and etch\$3 and mask\$3	USPAT; US-PGPUB	2002/11/06 10:55
-	922	channel adj waveguide	USPAT; US-PGPUB	2002/11/06 10:57
-	15	(ridged adj waveguide)and etch\$3 and mask\$3	USPAT; US-PGPUB	2002/11/01 09:21
-	206	waveguide and etch\$3 and mask\$3 and dicing	USPAT; US-PGPUB	2002/11/06 10:57
-	18	SF6 and O2 and CHF3 and etching	USPAT; US-PGPUB	2002/11/06 11:48
-	44	(channel adj waveguide)and etch\$3 and mask\$3 and chamber	USPAT; US-PGPUB	2002/11/01 09:50
-	312	waveguide and etch\$3 and mask\$3 and dic\$3	USPAT; US-PGPUB	2002/11/01 10:08
-	65	(channel adj waveguide)and etch\$3 and mask\$3 and facet	USPAT; US-PGPUB	2002/11/06 10:58
-	49	waveguide and etch\$3 and mask\$3 and facet and separat\$3 and dic\$3	USPAT; US-PGPUB	2002/11/04 13:00
-	48	waveguide same etch\$3 same mask\$3 same facet	USPAT; US-PGPUB	2002/11/04 13:01
-	25	etch\$3 adj glass same ("SF6.sub." or "NF3.sub." or (flourine near3 gas) or oxygen or "CHF3.sub." or HBr)	USPAT; US-PGPUB	2002/11/06 10:56
-	35	etch\$3 adj glass same ("SF.sub.6" or "NF.sub.3" or (flourine near5 gas) or oxygen or "CHF.sub.3" or HBr)	USPAT; US-PGPUB	2002/11/05 11:04
-	13	etch\$3 adj glass same ("SiF.sub.6" or "SiF.sub.4" or mTorr)	USPAT; US-PGPUB	2002/11/05 11:11
-	3	etch\$3 same ("SiF.sub.6" and "SiF.sub.4" and mTorr)	USPAT; US-PGPUB	2002/11/05 11:12
-	14	etch\$3 same ("SiF.sub.6" same "SiF.sub.4")	USPAT; US-PGPUB	2002/11/05 12:18
-	30	etch\$3 same inductive same plasma same ("noble gas" or argon or neon or helium)	USPAT; US-PGPUB	2002/11/05 11:18
-	95	etch\$3 same (HBr and "SiF.sub.4" and "CHF.sub.3")	USPAT; US-PGPUB	2002/11/05 12:20
-	57	etch\$3 same (("SiF.sub.6" or "SiF.sub.4") same HBr same "NF.sub.3" same "SF.sub.6")	USPAT; US-PGPUB	2002/11/06 10:59
-	6	((("5874362") or ("4776661") or ("5853960") or ("6235214") or ("4652290") or ("5710847"))).PN.	USPAT; US-PGPUB	2002/11/06 10:16
-	95	method adj2 forming near2 (optical adj (component or waveguide))	JPO; DERWENT	2002/11/06 10:55
-	5	(channel adj waveguide)and etch\$3 and mask\$3	JPO; DERWENT	2002/11/06 10:55
-	3	(optical adj waveguide).ti.and facet and etch\$3	JPO; DERWENT	2002/11/06 10:55
-	3	waveguide and etch\$3 and mask\$3 and dicing	JPO; DERWENT	2002/11/06 10:57
-	3	waveguide and etch\$3 and mask\$3 and facet	JPO; DERWENT	2002/11/06 10:57
-	174	etch\$3 same ("SiF.sub.6" or "SiF.sub.4" or mTorr)	JPO; DERWENT	2002/11/06 10:58
-	43	C4H8 or "C.sub.4H.sub.8" and etch\$3	USPAT; US-PGPUB	2002/11/06 11:51
-	35	C4H8 or "C.sub.4H.sub.8" same etch\$3	USPAT; US-PGPUB	2002/11/06 11:51
-	173	(optical adj waveguide)and etch\$3 same silica same silicon	USPAT; US-PGPUB	2002/11/06 15:10
-	9	(etch\$3 adj chamber) same (continuous adj etching)	USPAT; US-PGPUB	2002/11/07 09:35
-	40	etch\$3 same silicon same (".ANG./min" or "ang/min" or "microns/min")	USPAT; US-PGPUB	2002/11/07 09:38